

CHEMICAL RESISTANCE

Excellent Resistance at pH >13.5 and pH <1

Stress @ Yield (%)	1.5 IEC				2.0 IEC				Comments
	3 Day	7 Day	14 Day	30 Day	3 Day	7 Day	14 Day	30 Day	
Control	2400	-	-	-	2100				
Water	2600	2700	2700	2900	2300	1900	3400	3100	
10 wt% Hydrochloric Acid (2.7 N)	2200	2300	2300	2500	2500	2300	2000	2800	
10 wt % Nitric Acid (1.6 N)	1700	2400	2400	2400	2400	1800	2400	2700	
10 wt % Sulfuric Acid (2N)	2200	2400	2400	2500	2600	2300	2300	1900	
10 wt % Phosphoric Acid (3N)	2100	2300	2400	2100	2100	2000	2200	1900	
250 ppm Chlorine (NaOCl)	2200	2500	0	0	2500	3000	0	0	42k ppm-hr
15 wt % Sodium Chloride	2600	2600	2500	2700	2700	2700	2300	3100	
10 wt % Sodium Hydroxide (2.5N)	2300	2600	2600	2700	2700	3100	2500	2700	
10 wt % Ammonium Hydroxide (2.9 N)	2600	2600	2600	2600	3000	3600	3100	2600	

CHEMICAL RESISTANCE

Excellent Resistance at pH >13.5 and pH <1

Strain @ Break (%)	1.5 IEC				2.0 IEC			
	3 Day	7 Day	14 Day	30 Day	3 Day	7 Day	14 Day	30 Day
Control	90	-	-	-	40	-	-	-
Water	95	100	100	110	60	50	60	110
10 wt % Hydrochloric Acid	4	50	120	70	30	130	90	90
10 wt % Nitric Acid	3	150	130	10	90	30	20	120
10 wt % Sulfuric Acid	5	70	40	60	60	50	60	130
10 wt % Phosphoric Acid	20	230	200	10	30	80	130	20
250 ppm Chlorine	4	100	-	-	80	130	-	-
15 wt % Sodium Chloride	130	140	40	80	40	60	10	10
10 wt % Sodium Hydroxide	3	20	120	80	20	60	40	90
10 wt % Ammonium Hydroxide	110	110	70	170	100	30	60	200